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Microstructure and optical dispersion characterization of nanocomposite sol–gel TiO₂–SiO₂ thin films with different compositions



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HIGHLIGHTS

- Nanocomposites TiO₂-SiO₂ thin films were prepared by sol-gel dip-coating process.
- The composition-dependent structural and optical properties were examined.
- The refractive index dispersion fit well the Wemple-DiDomenico single oscillator model.
- The optical parameters were tunable by a simple control on the film composition.

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ABSTRACT

Nanocomposite TiO₂-SiO₂ thin films with different compositions (from 0 to 100 mol% TiO₂) were deposited by sol-gel dip-coating method on silicon substrate. Crystal structure, chemical bonding configuration, composition and morphology evolutions with composition were followed by Raman scattering, Fourier transform infrared spectroscopy, energy-dispersive X-ray spectroscopy and scanning electron microscopy respectively. The refractive index and the extinction coefficient were derived in a broad band wavelength (250-900 nm) from spectroscopic ellipsometry data with high accuracy and correlated with composition and microstructure. Results showed an anatase structure for 100% TiO₂ with a grain size in 6-10 nm range. Whereas, the inclusion of SiO₂ enlarges the optical band gap and suppresses the grain growth up to 4 nm in size. High TiO₂ dispersion in SiO₂ matrix was observed for all mixed materials. The refractive index (at λ = 600 nm) increases linearly with composition from 1.48 (in 100% SiO₂) to 2.22 (in 100% TiO₂) leading to lower dense material, its dispersion being discussed in terms of the Wemple-DiDomenico single oscillator model. Hence, the optical parameters, such optical dispersion energies E_0 and E_d , the average oscillators, strength S_0 and wavelength λ_0 and the ratio of the carrier concentration to the effective mass N/m^* have been derived. The analysis revealed a strong dependence on composition and structure. The optical response was also investigated in term of complex optical conductivity (σ) and both volume and surface energy loss functions (VELF and SELF).

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Introduction

Combining various different compounds (composite materials) has attracted a great deal of attention in the recent years, in the goal to achieve novel materials with structural, optical or electrical properties different from those of the individual pure materials. By now, various combinations (binary, ternary or more) have been investigated using a variety of inorganic oxides such as TiO₂, SiO₂, ZrO₂, CaO, CeO₂, MgO and Al₂O₃ [1–6].

Because of the large difference between their optical constants of band gap and refractive index, TiO_2 and SiO_2 appear well suited for these purposes and several advantages can be derived from their binary composite. Both TiO_2 and SiO_2 are typical optical thin films with high transparency and low absorption in visible and near infrared regions. Furthermore, as they are low cost, safe and abundant materials with high chemical, thermal and mechanical stabilities, they have been widely used for various optical applications, such as antireflective coatings [6,7], high reflecting, mirrors [8], photocatalyst [9] and integrated optical waveguides [10].

To our knowledge, Although many studies have investigated TiO_2 -SiO₂ composites films [8,9,11,12], detailed correlation between microstructure and optical parameters such as dielectric functions or dispersion parameters have not yet been reported.

The aim of this work was to investigate the influence of the composition nanocomposite $TiO_2 -SiO_2$ thin films on their microstructure, optical and electrical properties. For this purpose, films with different compositions as well as the single materials have been elaborated by a sol–gel process and dip-coated on (100) polished silicon. Structural and elementary characterizations were carried out with Raman and Fourier Transform Infrared Spectroscopy (FTIR) characterization respectively while the nanostructure was observed by Scanning Electron Microscopy (SEM). The optical properties were studied using spectroscopic ellipsometry (SE) in a large spectral range of 250–900 nm which represents the major motivation of our work.

Experimental

Silica coating sols were prepared by refluxing at 80 °C under stirring for 90 min a mixture of silicon tetraethoxide (TEOS) (TEOS, Aldrich 99.99%), propanol (Prolabo 99.5%) as solvent, H₂O as hydrolysis agent and HCl (Cheminova 37 wt%) as acid catalyst. The molar ratio of TEOS/2-Propanol/H₂O was 1:42:4. For Titania sols a mixture of titanium tetra-isopropoxide (TTIP, Fluka 99.99%), iso-propanol as solvent, acetylacetone (acacH, Aldrich 99%) as ligand, and water as hydrolysis agent and acetic acid as an acid catalyst were stirred under room temperature for 30 min with the molar ratio. The molar ratio of TTIP/2-Propanol/acacH/ H₂O is 1:30.6:0.3:4. The sols for composite materials were prepared by mixing for 2 h the same sol prepared for single titania (with $H_2O/TEOS$ equal to 2) with the same sol prepared for single silica (pre-refluxed only for 30 min) with different compositions (25, 50 and 75 mol%TiO₂). But the water silicon tetraethoxide molar ratio was kept equal to two in this case, and the sol was pre-refluxed only for 30 min.

The film deposition was carried out on silicon wafers by dipping-withdrawing at 50 mm/minute speed in an ambient atmosphere. Afterwards, the samples were dried at 100 °C followed by sintering in air at 500 °C for 1 h.

Characterization

The phase structure was investigated by micro-Raman spectrometer (Jobin–Yvon T64000) working in back-scattering configuration. The excitation line at λ = 514.5 nm was provided by Ar–Kr ion laser. The chemical structure identification was performed with FTIR Thermo Nicolet NEXUS 670. Scanning electronic microscope (SEM) (JEOL JSM-6360LV) equipped with energydispersive X-ray spectroscopy (EDS) was used to investigate the surface morphology and the composition. The relationship of ellipsometric angles with wavelength were recorded with a phase modulated spectroscopic ellipsometer (UVISEL, Horiba Scientific) at angle of 69.5° in the range of λ = 250 to λ = 900 nm with a step of 5 nm.

Results and discussion

Structural and morphological studies

Raman shift characterization

From Raman scattering spectra displayed in Fig. 1, we can observe only the active mode of silicon substrate located at 300, 425, 520, 617 and 660 cm⁻¹ in 75% TiO₂ sample [13]. Similar spectra were obtained for 25% TiO₂, 50% TiO₂ and 100% SiO₂ films confirming the amorphous structure. The 100% TiO₂ spectra shows the appearance of other extra features assigned to the allowed active modes of anatase structure determined by Ohsaka et al. [14], A_{1g} (515 cm⁻¹), $2B_{1g}$ (399 and 519 cm⁻¹), $3E_{g}$ (144,197 and 640 cm⁻¹).

The absence of any peak corresponding to anatase phase in the mixed films attests to the homogeneous and regular dispersion of Ti and Si atoms in the mixed films. This is in agreement with other works reporting the growth of amorphous sol–gel TiO₂–SiO₂ films annealed at 400 °C for low SiO₂ concentrations around 25% mole [15].

FTIR characterization

To follow clearly the effect of the heat-treatment on film structure, FTIR spectra were recorded on unsupported materials (in KBr pellets) corresponding to as deposited and sintered films of each composition. From Fig. 2(a) in all composition of unsintered samples, one can observe a broad band between 3255 and 3386 cm⁻¹ assigned to the fundamental stretching vibration of free or bonded hydroxyl groups belonging to adsorbed water, which are proved by a weak band at 1630 cm⁻¹ [16]. The weak band at 2975 cm⁻¹ is attributed to -C-H stretching vibration [17]. The bands at 1110, 1350, 1433 and 1543 cm⁻¹ are assigned to wagging, rocking and scissoring of the $-CH_2$ vibration from acetyl and propoxide groups of organic compounds. However, those between 573 and 657 cm⁻¹ are assigned to C–H deformation mode [18]. The bands below 445 cm⁻¹ are assigned to stretching modes of Si–O and Ti–O vibrations [19]. Whereas the band at 740 cm⁻¹ belongs to the Ti–O



Fig. 1. Raman spectra of thin 75% TiO₂ and 100% TiO₂ films on Si substrate.

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